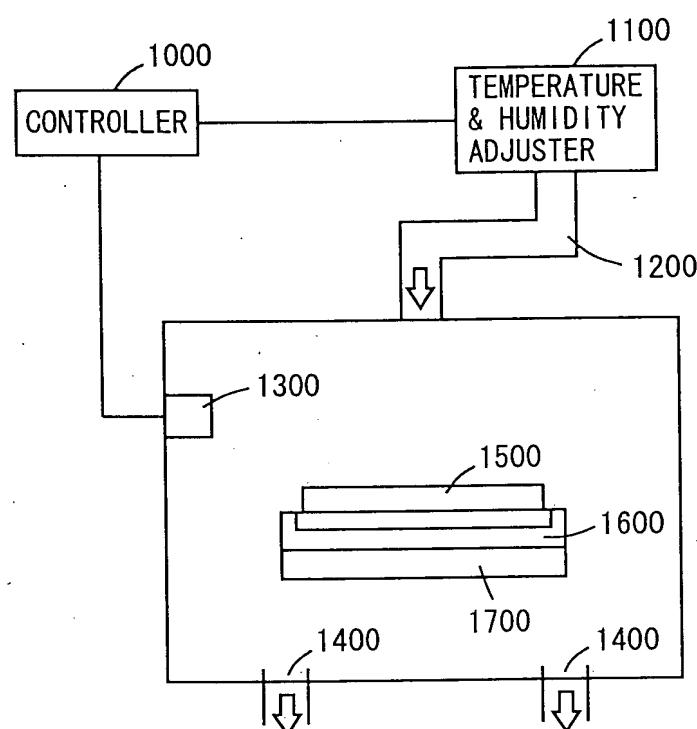
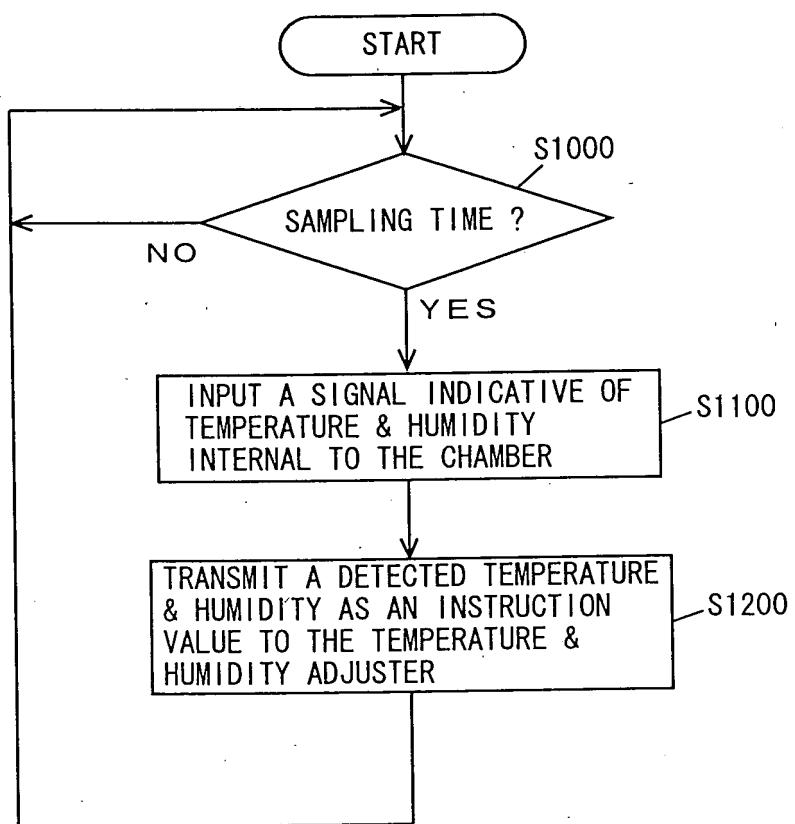


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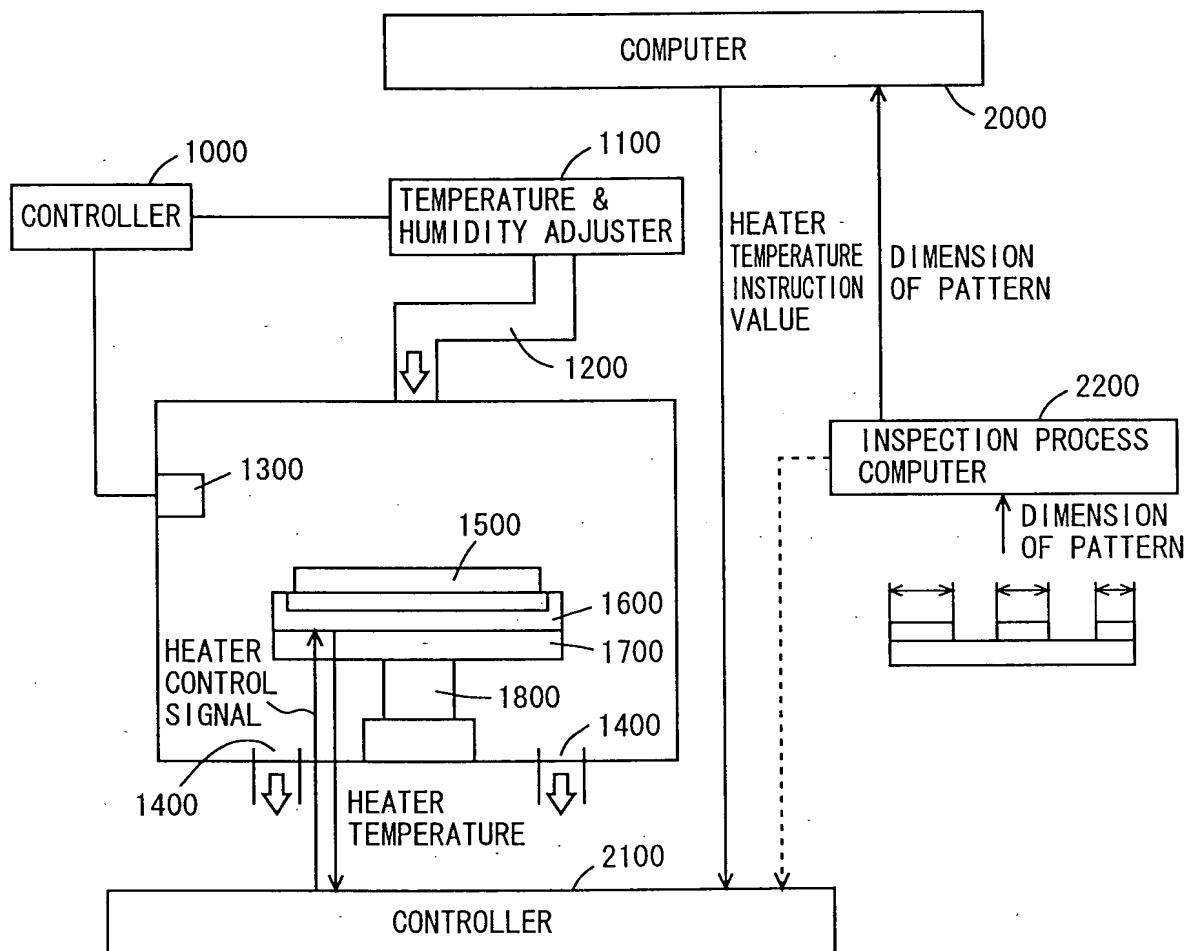
F I G. 1



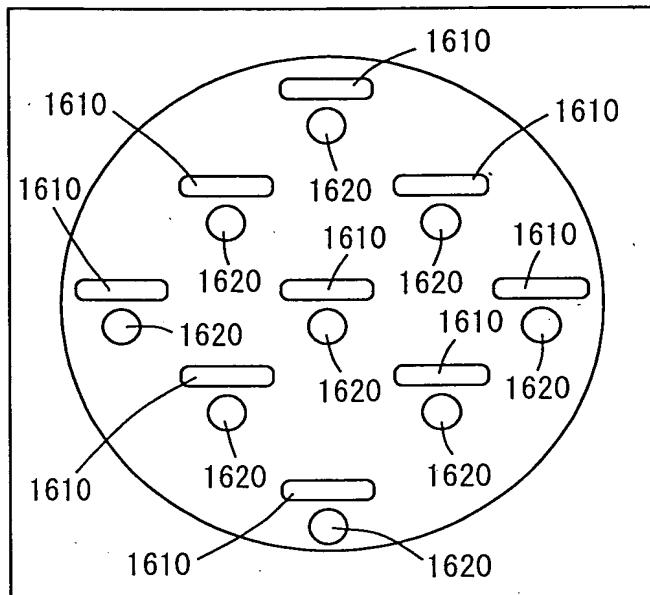
F I G. 2



F I G . 3



F I G. 4



F I G. 5

TYPE OF PRODUCT	TYPE OF PROCESS STEP	VARIATION IN DIMENSION PER UNIT TEMPERATURE (nm/deg.)
DRAM	1F	5
	TG	3
	1C	4
	1M	5
FLASH	1F	4
	1G	2
	1C	6
	1M	3
:	:	:
:	:	:

F I G. 6

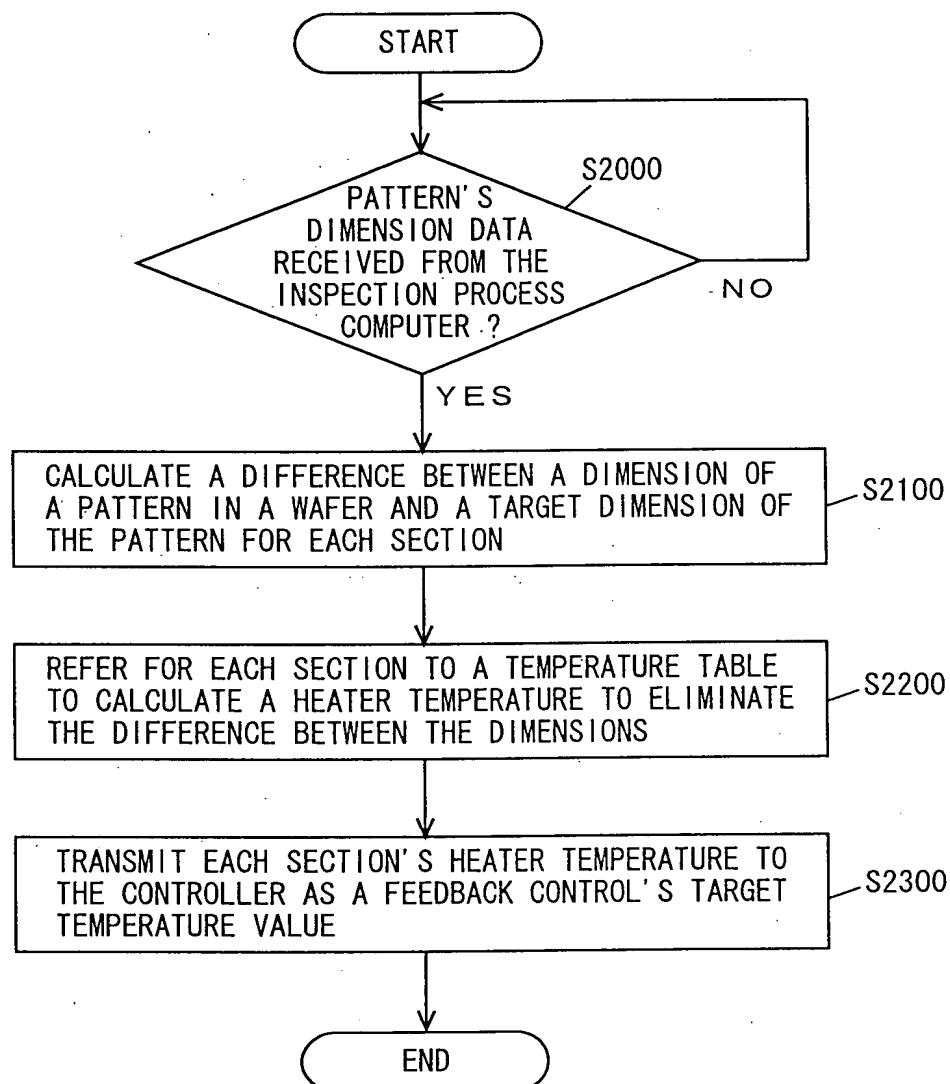
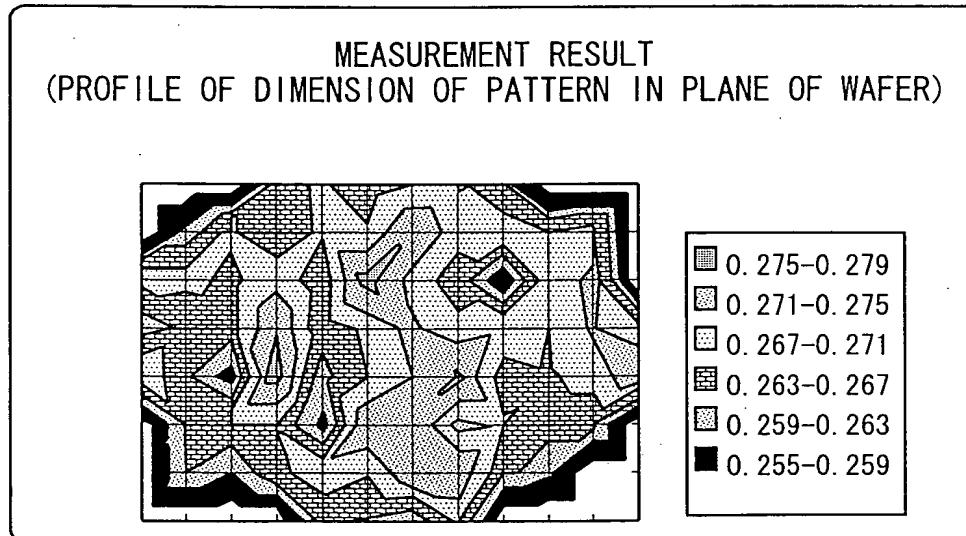


FIG. 7

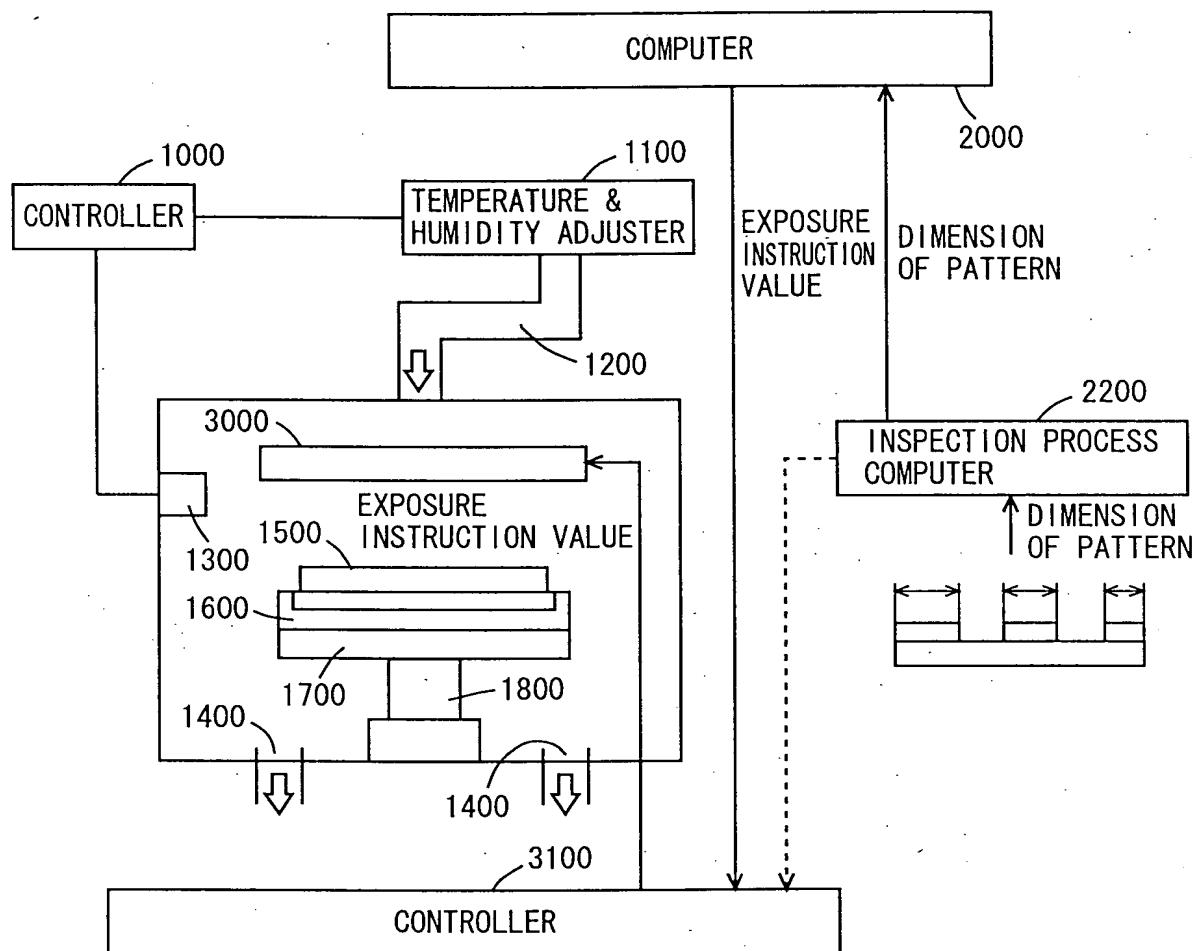
MEASUREMENT RESULT (LIST OF RESULT)		
NO.	Chip NO.	Data
1	00, 03	0. 2744
2	00, 04	0. 2688
3	01, 02	0. 2641
4	01, 03	0. 2686
5	01, 04	0. 2713
6	01, 05	0. 2716
...
...
...
...

20 28 36 44 52 59
7 13 19 27 35 43 51 58 65 71
6 12 18 26 34 42 50 57 64 70 74
2 5 11 17 25 33 41 49 56 63 69 73
1 4 10 16 24 32 40 48 55 62 68 72
3 9 15 22 31 39 47 54 61 67
8 14 22 30 38 46 53 60 66
21 29 37 45

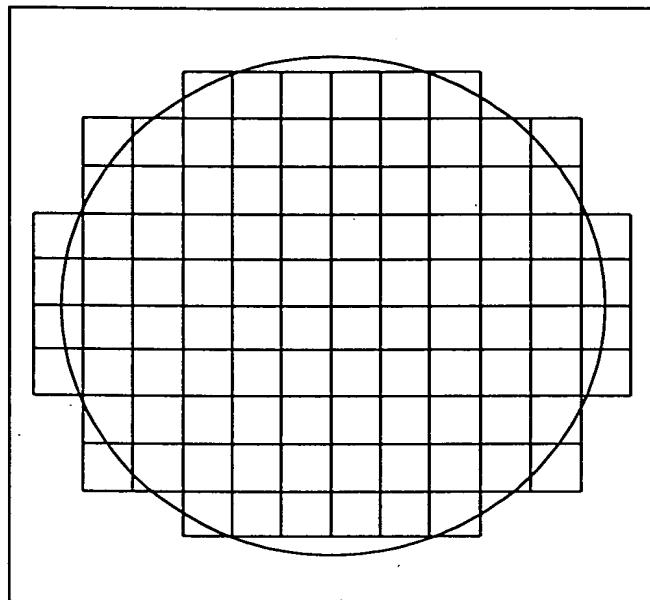
FIG. 8



F I G. 9



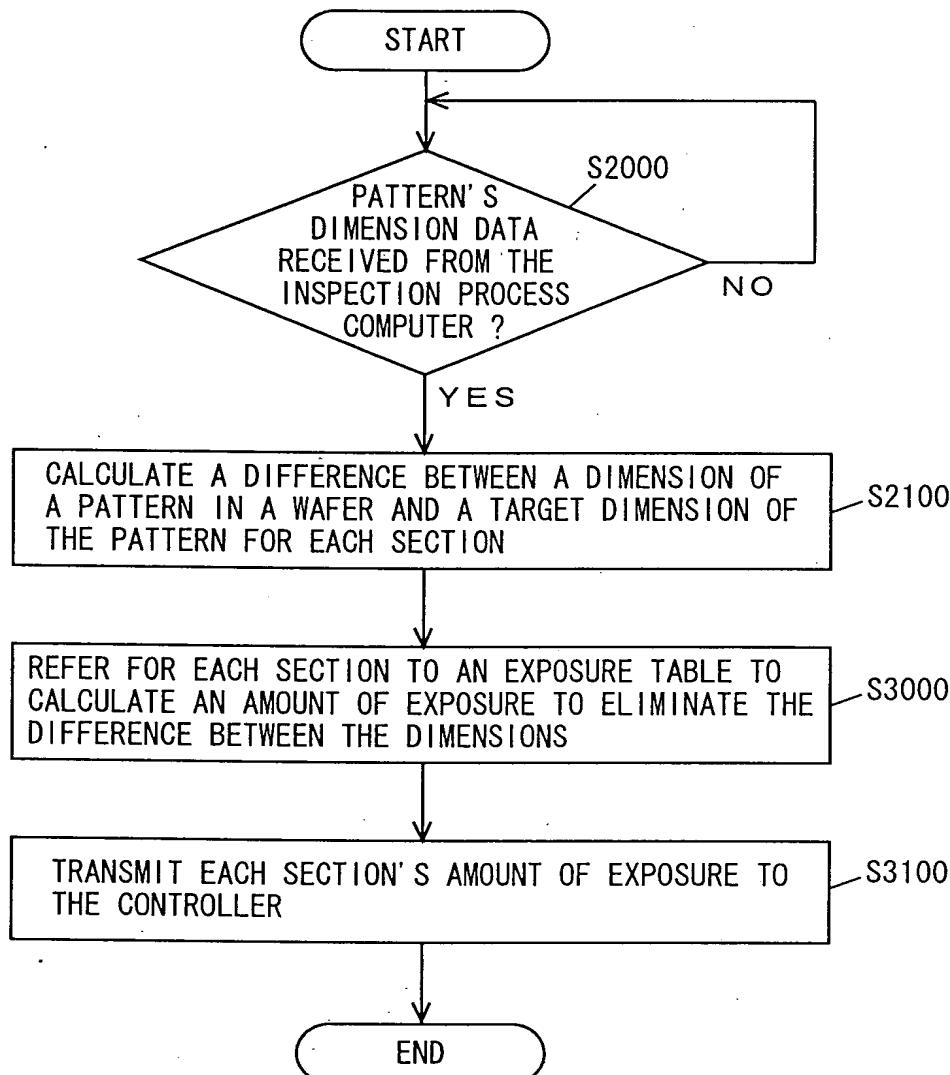
F I G. 1 0



F I G. 1 1

TYPE OF PRODUCT	TYPE OF PROCESS STEP	VARIATION IN DIMENSION PER UNIT AMOUNT OF EXPOSURE (nm/msec)
DRAM	1F	2
	TG	2
	1C	1
	1M	4
FLASH	1F	3
	1G	2
	1C	3
	1M	4
:	:	:
:	:	:

F I G. 1 2



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F I G. 13

	249	257	256	258	254	257						
254	257	248	254	254	256	252	254	256	257			
255	254	251	252	255	249	249	252	248	257	258		
251	250	252	254	249	250	248	248	252	251	254	256	
255	253	252	252	248	253	251	248	249	250	252	257	
248	252	252	251	249	256	251	248	252	252	252		
	254	249	250	248	255	250	251	251	253	254		
		254	253	257	257							